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104 also
corresponds to initializing the timer of the computer to
correspond to the
running time of the program. Every 1/18th of a second
corresponds to one count
in the timer. Therefore, the counter which is initialized at
the beginning of
the call of the program to zero is incremented by one at every
1/18th second
time interval. Block 104 corresponds to setting up of the
following interrupts
which are used during the running of the control system. Set
system timer
interrupt to point to a subroutine which counts events. When
sufficient counts
have been received to allow an event (e.g. plot the data on
the screen) a flag
is set in the interrupt routine, which is then read and acted
on accordingly by
the program during normal operation. After execution of the
interrupt
subroutine, program execution resumes at the point at which
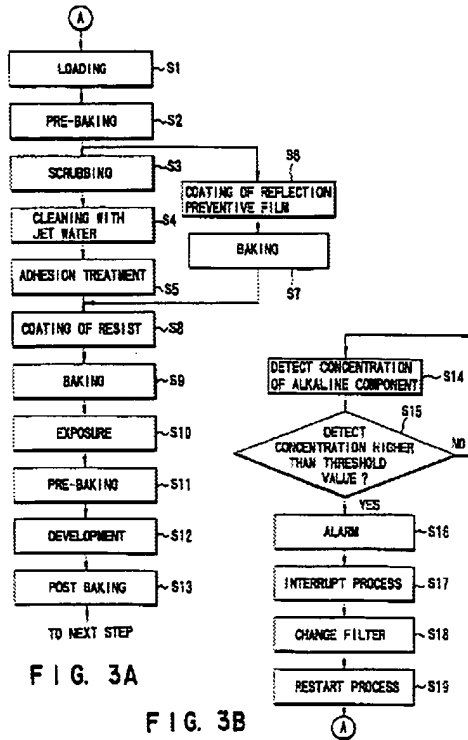the interrupt

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	U	1	Document ID	Issue Da	Pag	Current O	Current XR	
1			US 20030123	20030703	78	382/104		System f
2			US 20030123	20030703	79	382/104		System f
3			US 20010011	20010802	39	713/200		Secure m
4			US 6587573	20030701	78	382/104	340/930;	System f
5			US 6413616	20020702	42	428/167	428/168;	Building
6			US 6412072	20020625	36	713/200		Parasiti
7			US 6219789	20010417	37	713/200		Micropro
8			US 6165562	20001226	42	427/421	427/280;	Building
9			US 6150645	20001121	37	219/715	219/702;	Radiatio
10			US 6097019	20000801	34	219/750	219/702	Radiatio
11			US 6097006	20000801	20	219/497	399/69	Fixing u
12			US 6094292	20000725	43	359/265	359/267;	Electroc
13			US 5953556	19990914	20	399/66		Electrop
14			US 5837978	19981117	29	219/702	219/705	Radiatio
15			US 5832207	19981103	39	713/200		Secure m
16			US 5565737	19961015	6	315/111.2	315/111.41	Aliasing
17			US 5460661	19951024	9	148/251	427/195;	Process
18			US 5385796	19950131	31	430/64	430/126;	Electrop

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FIG. 3A

FIG. 3B

protective film to the wafer W, while the resist coating unit
15b applies
photoresist to the wafer W. The developing section 20 is
formed adjacent to the
interface section 30 and has two developing units 22. Each of
the developing
units 22 develops the wafer W subjected to the exposing
process in an exposing
unit 40.

Detailed Description Text - DETX (18):
    The CPU 60 feedback-controls the conveying machine 6 of the
coating unit 10
and a drive motor 17 of a spin chuck 16. In accordance with a
program
transferred from the CPU 60, the process can be continued or
interrupted.

Detailed Description Text - DETX (20):
    Initially, the wafer moving mechanism 2 takes out a
non-processed wafer W
from the first cassette 1a of the cassette station 4 in a
loader/unloader
section, and then places the non-processed wafer W on the
holder 3 while
centering the wafer W. The main conveying machine 6 picks up
the wafer W from
the holder 3 by the arm 7 and holds the same to introduce the
wafer W into the
processing section (step S1). Then, the main conveying
machine 6 introduces

	U	I	Document ID	Issue Da	Pag	Current O	Current XR	
37			US 6197418	20010306	7	428/332	427/108;	Electroc
38			US 6194127	20010227	9	430/313	216/102;	Resistiv
39			US 6162745	20001219	19	438/795	257/E21.02	Film for
40			US 6159645	20001212	6	430/25	430/28	Black ma
41			US 6144435	20001107	50	349/133	349/122;	Liquid c
42			US 6124606	20000926	14	257/291	257/386;	Method o
43			US 6107009	20000822	25	430/331	510/176	Photores
44			US 6099980	20000808	7	428/690	257/40;	Organic
45			US 6097469	20000801	16	355/30	396/611;	Method o
46			US 6066575	20000523	22	438/782	427/240;	Semicond

	Search Text	DBs
1	1 and subroutine	USPAT; US-PGPUB; DERWENT
2	5 and interrupt$3	USPAT; US-PGPUB; DERWENT
3	1 and interrupt same ((plural or parallel) near3 (timers or timing))	USPAT; US-PGPUB; DERWENT
4	1 and ((plural or parallel) near3 (timers or timing))	USPAT; US-PGPUB; DERWENT
5	1 and sub adj routine	USPAT; US-PGPUB; DERWENT
6	(algorithm or program) near4 (spin near2 coat$3 or (develop$4 or process$3) near4 (substrate or wafer))	USPAT; US-PGPUB; DERWENT
7	1 and ((timer or timing) or interrupt$3)	USPAT; US-PGPUB; DERWENT
8	(sequencer or computer near3 (program oe instruction or code)) near4 (spin near2 coat$3 or (develop$4 or process$3) near4 (substrate or wafer))	USPAT; US-PGPUB; DERWENT

05/14/2001, EAST Version: 1.02.0008

	Search Text	DBs
9	29 and ((timer or timing) or interrupt$3)	USPAT; US-PGPUB; DERWENT

	Search Text	DBs
1	(processing or develop$4 or coat$3) near3 (substrate or wafer or lcd)	USPAT; US-PGPUB; DERWENT
2	serial near4 (timing or control or process$3) same (sub adj routines or subroutine)	USPAT; US-PGPUB; DERWENT
3	5 same interrupt$3 near6 execut$3 near4 commend	USPAT; US-PGPUB; DERWENT
4	5 same interrupt$3 same execut$3 near4 commend	USPAT; US-PGPUB; DERWENT
5	5 and interrupt$3 same execut$3 near4 commend	USPAT; US-PGPUB; DERWENT
6	1 and 21	USPAT; US-PGPUB; DERWENT
7	1 and 5	USPAT; US-PGPUB; DERWENT
8	5 and interrupt$3	USPAT; US-PGPUB; DERWENT

	Search Text	DBs
9	1 and 33	USPAT; US-PGPUB; DERWENT
10	5 and interrupt$3 same subroutine	USPAT; US-PGPUB; DERWENT
11	1 and interrupt$3 same subroutine	USPAT; US-PGPUB; DERWENT
12	1 and timing adj chart	USPAT; DERWENT
13	45 and interrupt$3 same subroutine	USPAT; US-PGPUB; DERWENT
14	45 and interrupt$3	USPAT; US-PGPUB; DERWENT